

FORM PTO-1449  
(Modified)U.S. DEPARTMENT OF COMMERCE  
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**06425ZP**

SERIAL NO.

**INFORMATION DISCLOSURE  
STATEMENT BY APPLICANT**  
(Use several sheets if necessary)APPLICANT  
**Richard Van Court Carr, et al..**

FILING DATE

GROUP

(37 CFR 1.98(b))

**U.S. PATENT DOCUMENTS**

EXAM- INER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
<i>RC</i>	0 0 5 9 7 1 0	3/27/2003	Inoue	430	270.1	
<i>RC</i>	0 0 0 4 5 7 0	1/10/2002	A. Zampini, et al.	526	257	2/23/2001
<i>RC</i>	0 0 5 1 9 3 6	5/2/2002	Y. Harada, et al.	430	270.1	9/7/2001
<i>RC</i>	0 0 5 5 0 6 0	5/9/2002	G. N. Taylor, et al.	430	270.1	9/8/2001
<i>RC</i>	0 0 6 1 4 6 4	5/23/2002	T. Aoi, et al.	430	270.1	9/25/2001
<i>RC</i>	6 2 9 1 1 3 0	9/18/2001	K. Kodama, et al.	430	270.1	7/27/1999
<i>RC</i>	6 4 0 6 8 2 8	6/18/2002	C. R. Szmanda, et al.	430	270.1	2/24/2000

**FOREIGN PATENT DOCUMENTS**

	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION YES NO
<i>RC</i>	JP 2 1 7 9 7 3 1		Japan (Abstract)			X
<i>RC</i>	WO 0 2 3 1 5 9 5		World	G03F	7/00	X
<i>RC</i>	EP 1 1 0 3 8 5 6		Europe	G03F	7/039	X
<i>RC</i>	EP 1 1 2 6 3 2 2		Europe	G03F	7/039	X
<i>RC</i>	WO 0 0 1 7 7 1 2		World	G03F	7/039	X
<i>RC</i>	WO 0 0 6 7 0 7 2		World	G03F	7/004	X
<i>RC</i>	WO 0 1 6 3 3 6 2		World	G03F	7/00	X
<i>RC</i>	WO 0 1 8 5 8 1 1		World	G03F	2/14/00	X
<i>RC</i>	WO 0 2 2 1 2 1 2		World	G03F	7/004	X
<i>RC</i>	WO 0 2 2 1 2 1 3		World	G03F	7/004	X
<i>RC</i>	WO 0 2 2 1 2 1 4		World	G03F	7/004	X
<i>RC</i>	WO 0 2 2 1 2 1 6		World	G03F	7/039	X

**OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)**

<i>RC</i>	Hiroshi Ito, et al., "Synthesis and Evaluation of Alicyclic Backbone Polymers for 193 nm Lithography", American Chemical Society, 1998.
<i>RC</i>	Hiroshi Ito, et al., "Aliphatic Platforms for the Design of 157 nm Chemically Amplified Resists", SPIE Proceedings, Vol. 4690 (2002), 18-28.
<i>RC</i>	M. M. Dhangra, et al., "Polymerization of 1,1,1-Trifluoroacetone with Aliphatic Secondary Amines. A Proton and Fluorine Magnetic Resonance Investigation," Organic Magnetic Resonance, Vol. 9, No. 1 (1977), pp. 23-28.
<i>RC</i>	H. E. Simmons, et al., "Fluoroketones" The Central Research Department Station, E. I. du Pont de Nemours and Co., Vol. 82 (1959), pp. 2288-2296.
<i>RC</i>	E. T. McBee, et al., "The Chemistry of 1,1,1-Trifluoropropanone. II. The Reactions of 4-Methyl-1,1,1,5,5,5-hexafluoro-3-penten-2-one with Methylmagnesium Iodide," The Department of Chemistry, Purdue University (1956), pp. 4597-4598.
<i>RC</i>	A. L. Henne, et al., "Trifluoromethylated Butadienes," The Department of Chemistry at The Ohio State University (1954), pp. 5147-5148.
<i>RC</i>	K. J. Pryzbilla, et al., "Hexafluoroacetone in Resist Chemistry: A Versatile New Concept for Materials for Deep UV Lithography," SPIE Advances in Resist Chemistry and Process IX Vol. 1672 (1992).
<i>RC</i>	M. K. Crawford, et al., "New Materials for 157 nm Photoresists: Characterization and Properties," SPIE Advances in Resist Chemistry and Processing IX Vol. 3999 (2000).
<i>RC</i>	R. R. Dammel, et al., "New Resin Systems for 157 nm Lithography," Journal of Photopolymer Science and Technology, Vol. 14 No. 4 (2001).
<i>RC</i>	H. Ito, et al., "Development of 157 nm Positive Resists," J. Vac. Sci. Technol. B 19(6) (2001).
<i>RC</i>	H. Ito, "Dissolution Behavior of Chemically Amplified Resist Polymers for 248-, 193-, and 157-nm Lithography," J. Res. & Dev. Vol. 45 No. 5 (2001).
<i>RC</i>	S. Cho, et al., "Investigation of a Fluorinated ESCAP based resist for 157 nm Lithography," (2001).
<i>RC</i>	K. Patterson, et al., "The Challenges in Materials Design for 157 nm Photoresists," Lithography, Solid State Technology, pp. 41-48 (2000).

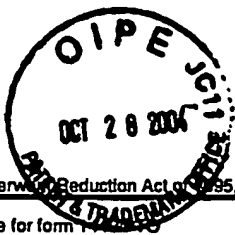
EXAMINER

*R. Karp*

DATE CONSIDERED

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<b>INFORMATION DISCLOSURE STATEMENT BY APPLICANT</b> (Use as many sheets as necessary)				<b>Complete if Known</b>	
				Application Number	10/784,377
				Filing Date	February 23, 2004
				First Named Inventor	Richard Van Court Carr, et al.
				Art Unit	1752
				Examiner Name	
Sheet	1	of	1	Attorney Docket Number 06425ZP USA	

U. S. PATENT DOCUMENTS					
Examiner Initials*	Cite No. <sup>1</sup>	Document Number	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		Number-Kind Code <sup>2</sup> (if known)			
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FOREIGN PATENT DOCUMENTS						
Examiner Initials*	Cite No. <sup>1</sup>	Foreign Patent Document	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	T <sup>6</sup>
		Country Code <sup>3</sup> Number <sup>4</sup> Kind Code <sup>5</sup> (if known)				
RL		JP2004107277A (Abstract Also Included)	04-08-2004	Takashi, et al.		✓

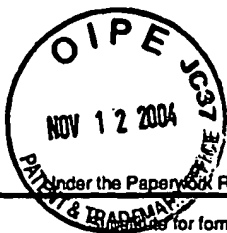
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				Application Number	10/784,377
				Filing Date	02/23/2004
				First Named Inventor	Richard Van Court Carr, et al.
				Art Unit	1752
				Examiner Name	
Sheet	1	of	1	Attorney Docket Number 06425ZP USA	

U. S. PATENT DOCUMENTS					
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FOREIGN PATENT DOCUMENTS						
Examiner Initials*	Cite No. <sup>1</sup>	Foreign Patent Document	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	T <sup>6</sup>
		Country Code <sup>3</sup> Number <sup>4</sup> Kind Code <sup>5</sup> (if known)				
PK		WO 00/67072	11/09/2000	Du Pont		

Examiner Signature	<i>Rygo</i>	Date Considered	4/15/06
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